

# WEST

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### Search Results -

Terms	Documents	
L4 and (low near2 K)	5	

	US Patents Full-Text Database	Ē
	US Pre-Grant Publication Full-Text Database	00000
	JPO Abstracts Database	***************************************
	EPO Abstracts Database	-
	Derwent World Patents Index	
Database:	IBM Technical Disclosure Bulletins	Ī

Search:

L5			Refine Search
	ext 👄   Cle	ear	-

#### Search History

DATE: Monday, April 21, 2003 Printable Copy Create Case

Set Nam side by sid		Hit Count	Set Name result set
DB=U	JSPT; PLUR=YES; OP=ADJ		
<u>L5</u>	L4 and (low near2 K)	5	<u>L5</u>
<u>L4</u>	L3 and (low adj dielectric)	33	<u>L4</u>
<u>L3</u>	L2 and (gate near2 contact)	1066	<u>L3</u>
<u>L2</u>	L1 and ( second near2 contact)	4259	<u>L2</u>
Ll	fet or (field adj effect adj transistor)	66854	L1

**END OF SEARCH HISTORY** 



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**Generate Collection** 

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## **Search Results -** Record(s) 1 through 5 of 5 returned.

1. Document ID: US 6534837 B1

L5: Entry 1 of 5

File: USPT

Mar 18, 2003

US-PAT-NO: 6534837

DOCUMENT-IDENTIFIER: US 6534837 B1

TITLE: Semiconductor device

Full | Title | Citation | Front | Review | Classification | Date | Reference | Sequences | Attachments | Claims | KWIC |
Draw Desc | Image |

2. Document ID: US 6492249 B2

L5: Entry 2 of 5

File: USPT

Dec 10, 2002

US-PAT-NO: 6492249

DOCUMENT-IDENTIFIER: US 6492249 B2

TITLE: High-K gate dielectric process with process with self

aligned damascene contact to damascene gate and a low-k inter level

dielectric

Full Title Citation Front Review Classification Date Reference Sequences Attachments Claims KoolC Draws Description

3. Document ID: US 6291278 B1

L5: Entry 3 of 5

File: USPT

Sep 18, 2001

US-PAT-NO: 6291278

DOCUMENT-IDENTIFIER: US 6291278 B1

TITLE: Method of forming transistors with self aligned damascene

gate contact

Full | Title | Citation | Front | Review | Classification | Date | Reference | Sequences | Attachments | Claims | KMC | Draw, Desc | Image |

4. Document ID: US 6271132 B1

L5: Entry 4 of 5

File: USPT

Aug 7, 2001

US-PAT-NO: 6271132

DOCUMENT-IDENTIFIER: US 6271132 B1

TITLE: Self-aligned source and drain extensions fabricated in a

damascene contact and gate process

Full Title Citation Front Review Classification Date Reference Sequences Attachments Claims KWC Drawu Desc - Image

5. Document ID: US 5935766 A

L5: Entry 5 of 5

File: USPT

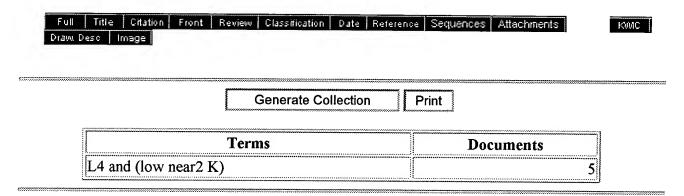
Aug 10, 1999

US-PAT-NO: 5935766

DOCUMENT-IDENTIFIER: US 5935766 A

TITLE: Method of forming a conductive plug in an interlevel

dielectric



**Display Format: Change Format** 

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